

ABSTRACT OF THE DISCLOSURE

To provide a cleaning processing method and a cleaning processing apparatus which can improve cleaning efficiency.

- 5 The apparatus is structured to install processing
units 11a - 11d which provide more than one kind of chemical
liquids out of a plurality of chemical liquids A - C for
processing wafers W, and to enable the same kind of a
processing liquid to be provided for at least two processing
10 units, and, upon successively processing objects-to-be-
processed which require their own processing sequences, to
consecutively load each object-to-be-processed W to a
processing unit which stores designated chemical liquid for
a processing sequence of the object-to-be-processed.